- 1 1. (original) A maskless lithography system comprising an array of blazed diffractive zone
- 2 plates, each of which focuses an energy beam into an array of images in order to create a
- 3 permanent pattern on an adjacent substrate.
- 1 2. (original) The maskless lithography system as claimed in claim 1, wherein said blazed
- 2 diffractive zone plates are blazed Fresnel zone plates.
- 1 3. (currently amended) [An] A maskless lithography system comprising an array of
- 2 apodized diffractive elements, each of which focuses an energy beam into an array of images in
- 3 order to create a permanent pattern on an adjacent substrate at a focal area and is apodized to
- 4 reduce at least one of the [main or] side lobes in an intensity distribution at a focal area.
- 1 4. (original) The maskless lithography system as claimed in claim 3, wherein apodized
- 2 diffractive elements are Fresnel zone plates.
- 5. (original) The maskless lithography system as claimed in claim 3, wherein apodized
- 2 diffractive elements are Fresnel phase plates.
- 1 6. (original) The maskless lithography system as claimed in claim 3, wherein apodized
- 2 diffractive elements are blazed Fresnel zone plates.
- 1 7. (original) The maskless lithography system as claimed in claim 3, wherein said apodized
- 2 diffractive elements are formed of photon sieves.
- 1 8. (original) The maskless lithography system as claimed in claim 7, wherein said photon

- 2 sieves are amplitude photon sieves.
- 1 9. (original) The maskless lithography system as claimed in claim 7, wherein said photon
- 2 sieves are phase photon sieves.
- 1 10. (original) The maskless lithography system as claimed in claim 7, wherein said photonic
- 2 sieves are alternating phase photonic sieves.
- 1 11. (original) A maskless lithography system comprising an array of diffractive elements,
- 2 each of which focuses an energy beam into an array of images in order to create a permanent
- 3 pattern on an adjacent substrate and has a focusing efficiency of at least 50%.
- 1 12. (original) The maskless lithography system as claimed in claim 11, wherein said
- 2 diffractive elements are 100% transmissive.
- 1 13. (original) The maskless lithography system as claimed in claim 12, wherein said
- 2 diffractive elements are alternating phase photon sieves.
- 1 14. (currently amended) A maskless lithography system comprising an array of [Besel]
- 2 Bessel zone plates, each of which [focuses an energy] converts an energy beam into an array of
- 3 [images] Bessel beams in order to create a permanent pattern on an adjacent substrate.